

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Applicant(s):** Cyril Cabral, Jr., et al.      **Examiner:** Long Pham  
**Serial No:** 10/662,900      **Art Unit:** 2814  
**Filed:** September 15, 2003      **Docket:** YOR920030218US1 (16714)  
**For:** REDUCTION OF SILICIDE      **Dated:** November 28, 2007  
FORMATION TEMPERATURE ON  
SiGe CONTAINING SUBSTRATES

**Confirmation No:** 1278

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO EX PARTE OUALYE OFFICE ACTION**

Sir:

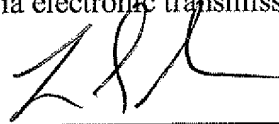
In response to the Office Action dated September 28, 2007, applicants submit the following amendments and remarks for entry into the record of the above-identified patent application.

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**CERTIFICATION OF ELECTRONIC TRANSMISSION**

I hereby certify that this document is being filed in the United States Patent and Trademark Office on the date shown below via electronic transmission.

Dated: November 28, 2007

  
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Leslie S. Szivos, Ph.D.